EE143 Lab Week 8

1) Lithography

Time (sec)				
Softbake:				
Exposure:				
Developer:				
Hardbake:		I		
Linewidth (um) of Photoresist				
Nominal	Measured		% Overetch	
2				
3				
4				
8				

Take a photo of the linewidth marks

Vernier Misalignment:	
_	•
X	
Y	

Take 3 Photos: Overall Vernier Pattern, and zoomed photo of X & Y vernier patterns

2) Aluminum:

Aluminum Etch Time:				
Linewidth (um) of Al after etch				
Nominal	Measured	.% Overetch		
2				
3				
4				
8				
Sintering:				
Time (min)				
Temperature (C)				

Questions:

Calculate % overetch of the linewidth patterns

What was a visual method for determining completion of etching?

Calculate theoretical Al thickness from etch time.

Calculate theoretical Al thickness from the sheet resistance.